

# PIEZOELECTRIC PLATEN DESIGN FOR IMPROVING PERFORMANCE IN CMP APPLICATIONS

5

## ABSTRACT OF THE DISCLOSURE

An invention is disclosed for improved performance in a CMP process using piezoelectric elements as a replacement for a platen air bearing. In one embodiment, a platen for improving performance in CMP applications is disclosed. The platen includes a plurality of piezoelectric elements disposed above the platen. In operation, the piezoelectric elements are used to exert force on the polishing belt during a CMP process. In this manner, zonal control is provided during the CMP process.